

Comparison of sulfamethoxazole and ciprofloxacin degradation by UV/H₂O₂ process

Hai-yan Yang^a, Yi-hua Chen^{b,*}, Jiu-min Jia^c, Bo Yang^b, Qiu Jin^b, Guan-dong Sun^b

^aKey Laboratory of Urban Stormwater System and Water Environment (Ministry of Education), Beijing University of Civil Engineering and Architecture, Beijing 100044, China, email: yanghaiyan@bucea.edu.cn ^bSchool of Environment and Energy Engineering, Beijing University of Civil Engineering and Architecture, Beijing 100044, China, emails: 15527372448@163.com (Y.-h. Chen), 17888812532@163.com (B. Yang), jinqiu1507@163.com (Q. Jin), 15701572546@163.com (G.-d. Sun)

^cChina Construction Engineering Design Group Corporation Limited, Beijing 100037, China, email: jiajiumin126@126.com

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ABSTRACT

The rate constants of sulfamethoxazole (SMX) and ciprofloxacin (CIP) degradation as well as the removal of total organic carbon (TOC) by UV/H₂O₂ process was investigated under various parameters including different H_2O_2 dosage and initial pH values. The results indicated that both SMX and CIP were efficiently removed in UV/H₂O₂ process and they peaked at different pH values of 3 and 7 respectively, while CIP degradation was greater than that of SMX. TOC removal was decreased with the pH values increased in the degradation of SMX in UV/H₂O₂ process while no significant change for CIP with the pH values raised. Based on molecular structure analysis, the transformation of both sulfonamide bond and oxazole ring N–O band in SMX were more difficult than defluorination and change of piperazine ring in CIP.

Keywords: UV/H₂O₂; SMX; CIP; Degradation; Mineralization

* Corresponding author.